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Docket No.: 543822004700
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Siegfried SCHWARZL et al.

Application No.: 10/812,411

Confirmation No.: 1274

Filed: March 30, 2004

Art Unit: 1763

For: EUV LITHOGRAPHY SYSTEM AND CHUCK
FOR RELEASING RETICLE IN A VACUUM
ISOLATED ENVIRONMENT

Examiner: K. A. Moore

RESPONSE TO RESTRICTION REQUIREMENT

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the restriction requirement set forth in the Office Action mailed March 3, 2006, Applicant hereby provisionally elects claims 1 through 7 for continued examination without traverse.

The Examiner has required restriction between Group I, claims 1-7, drawn to a lithography apparatus, classified in class 250, subclass 492.1; Group II, claims 8-12, drawn to a chuck apparatus for holding a reticle during processing, classified in class 250, subclass 492.1; and Group III, claims 13-17, drawn to a method for providing a vacuum isolated environment, classified in class 250, subclass 492.1.

In the unlikely event that the transmittal form is separated from this document and the Patent Office determines that an extension and/or other relief is required, Applicant petitions for any required relief including extensions of time and authorize the Commissioner to charge the cost of such petitions and/or other fees due in connection with the filing of this document to **Deposit Account No. 03-1952** referencing 543822004700.

Dated: April 3, 2006

Respectfully submitted,

By 

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